Martijn F J Vos

List of Publications by Citations

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

9	176	5	9
papers	citations	h-index	g-index

9	224	4	3.06
ext. papers	ext. citations	avg, IF	L-index

#	Paper	IF	Citations
9	Atomic layer deposition of molybdenum oxide from (NtBu)2(NMe2)2Mo and O2 plasma. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2016**, 34, 01A103	2.9	78
8	Area-Selective Deposition of Ruthenium by Combining Atomic Layer Deposition and Selective Etching. *Chemistry of Materials*, **2019**, 31, 3878-3882	9.6	46
7	Atomic Layer Deposition of Cobalt Using H-, N-, and NH-Based Plasmas: On the Role of the Co-reactant. *Journal of Physical Chemistry C*, **2018**, 122, 22519-22529	3.8	23
6	Concepts and prospects of passivating contacts for crystalline silicon solar cells **2015**,		10
5	Atomic layer deposition of ruthenium using an ABC-type process: Role of oxygen exposure during nucleation. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2020**, 38, 062402	2.9	6
4	Isotropic plasma atomic layer etching of Al2O3 using a fluorine containing plasma and Al(CH3)3. *Applied Physics Letters*, **2020**, 117, 162107	3.4	5
3	Plasma-Enhanced Atomic Layer Deposition of Cobalt and Cobalt Nitride: What Controls the Incorporation of Nitrogen?. *Journal of Physical Chemistry C*, **2020**, 124, 22046-22054	3.8	3
2	Reaction Mechanisms during Atomic Layer Deposition of AlF Using Al(CH) and SF Plasma. *Journal of Physical Chemistry C*, **2021**, 125, 3913-3923	3.8	3
1	Atomic layer deposition and selective etching of ruthenium for area-selective deposition: Temperature dependence and supercycle design. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 032412	2.9	2